

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

#2a
NEAL

In re application of

Tsuyoshi NAKAMURA, et al.

Application No.: To be assigned

Group Art Unit: To be assigned

Confirmation No.: To be assigned

Examiner: To be assigned

Filed: July 11, 2001

For: NOVEL COPOLYMER, PHOTORESIST COMPOSITION, AND PROCESS FOR
FORMING RESIST PATTERN WITH HIGH ASPECT RATIO

PRELIMINARY AMENDMENT

Commissioner for Patents
Washington, D.C. 20231

Sir:

IN THE CLAIMS:

Please enter the following amended claims:

9. (Amended) A novel copolymer according to claim 1, wherein said novel copolymer has a weight average molecular weight (Mw) in terms of polystyrene of from 7000 to 30000 and a molecular-weight distribution (Mw/Mn, where Mn is a number average molecular weight) of equal to or less than 3.5.

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